

ABSTRACT

An object of the present invention is to provide a ceramic heater for a semiconductor producing/examining device wherein a scattering in the resistance value of its resistance heating element is hardly generated and its heating face is excellent in temperature evenness. The present invention is a ceramic heater for a semiconductor producing/examining device having a resistance heating element formed on a surface of a ceramic substrate, wherein a gutter is formed along the direction of current flowing through the resistance heating element.